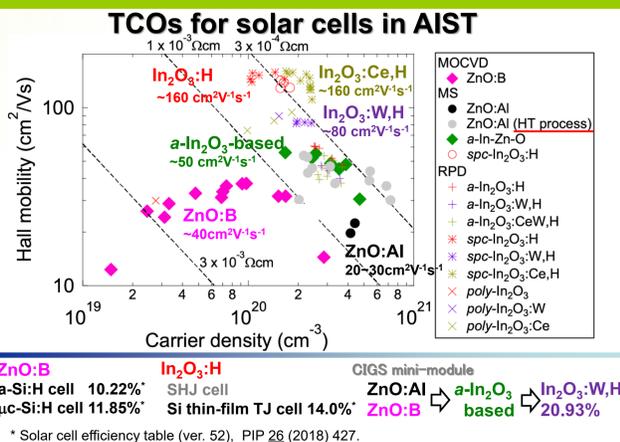


# Cu(In,Ga)Se<sub>2</sub> mini-modules with high-mobility In<sub>2</sub>O<sub>3</sub>:W,H transparent conducting oxide layers

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## Introduction

High transparency with low  $R_{sheet}$  ( $< 10 \Omega/sq$ ) and low  $T_g$  ( $< 200^\circ C$ ) is required for transparent front electrodes in integrated Cu(In,Ga)Se<sub>2</sub> (CIGS) based modules. ZnO-based transparent conductive oxide (TCO) are usually used as the front electrodes. Alternatively, an In<sub>2</sub>O<sub>3</sub>-based TCO that is normally used in silicon heterojunction solar cells could replace the ZnO-based TCOs because higher conductance and lower free carrier absorption with improved environmental stability can easily be achieved at low deposition temperatures. In this study, we applied In<sub>2</sub>O<sub>3</sub>:W,H layers to CIGS mini-modules and show the advantage of high-mobility In<sub>2</sub>O<sub>3</sub>-based TCOs by demonstrating a very high module efficiency (d.a.) of 20.93%. Remaining issues to be solved to achieve higher conversion efficiency will also be discussed.



## Summary

- High  $J_{sc} \times FF$  is demonstrated in CIGS mini-modules by high- $\mu$  In<sub>2</sub>O<sub>3</sub>:W,H TCO layer.
  - $J_{sc}$ : 1.5 – 2.0 mA up (vs ZnO/ZnO:Al reference)
  - FF: 0.775
- $V_{oc}$  is independent of the TCO layers, being determined by free-hole density in the CIGS layer.
  - $V_{oc}$ : 0.770 V per subcell
- ZnO/In<sub>2</sub>O<sub>3</sub>:W,H window layers achieve a high  $\eta$  of 20.93% (d.a.) in a mini-module structure.

**Points to be improved**

- High resistance TOS layer for the In<sub>2</sub>O<sub>3</sub>-based TCOs, Gridded module structure, Metastable free-hole density, Heat resistive junction

## Purpose and Experimental

### Purpose

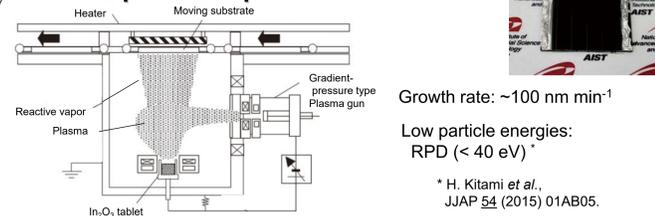
Impact of high- $\mu$  In<sub>2</sub>O<sub>3</sub>-based TCO  
Possibility of amorphous TOS as a high resistance layer ( $\leftarrow$  Large  $\Delta E_c$  at Mg<sub>x</sub>Zn<sub>1-x</sub>O/In<sub>2</sub>O<sub>3</sub> may affect transport in future...)

### Device structure

ZnO:Al/ZnO/CdS/CIGS/Mo/SLG (reference)  
In<sub>2</sub>O<sub>3</sub>:W,H/ZnO/CdS/CIGS/Mo/SLG  
In<sub>2</sub>O<sub>3</sub>:W,H/a-In-Ga-Zn-O/CdS/CIGS/Mo/SLG

CIGS (2  $\mu m$ ): co-evapo. GGI ratio :  $\sim 0.4$   
KF- and NaF- PDT  
CdS (30 nm): CBD  
i-ZnO, a-In-Ga-Zn-O (50 nm): MS  
AZO (720 nm), IWOH (560 nm): MS, RPD  
MgF<sub>2</sub> (110 nm): evapo.  
Size :subcell (5 mm  $\times$  20 mm)  $\times$  4

### Reactive plasma deposition

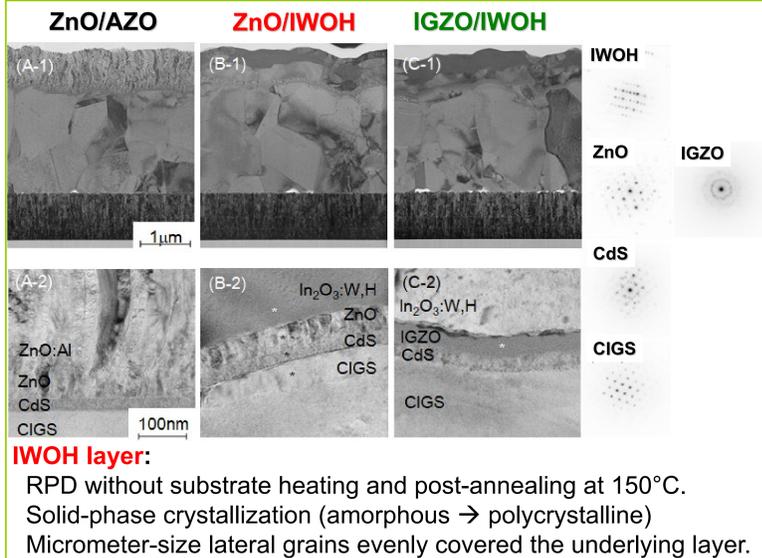


### Process after device fabrication

Dark Heating (150°C, 30 min)  
 $\rightarrow$  Relaxed state  
Heat Light Soaking (90°C,  $\sim 0.5 sun$ , 100 h)  
 $\rightarrow$  Metastable state

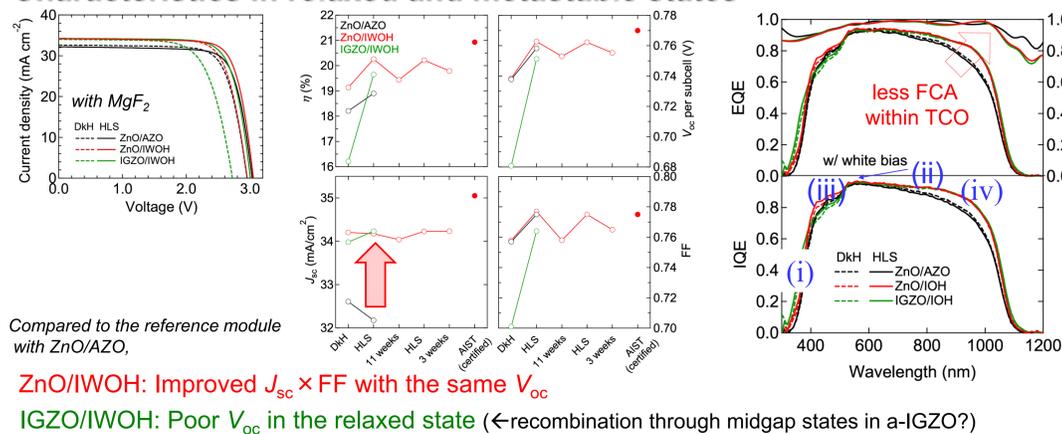
material	Thickness (nm)	$R_{sheet}$ ( $\Omega sq^{-1}$ )	$\rho$ ( $\Omega cm$ )	$N$ ( $cm^{-3}$ )	$\mu$ ( $cm^2 V^{-1} s^{-1}$ )
ZnO:Al	720	8.0	$5.8 \times 10^{-4}$	$4.5 \times 10^{20}$	24
In <sub>2</sub> O <sub>3</sub> :W,H	560	5.8	$3.3 \times 10^{-4}$	$2.6 \times 10^{20}$	74

## Structural property



## J-V, EQE characteristics (effects of window layers, metastable characteristics)

### Characteristics in relaxed and metastable states

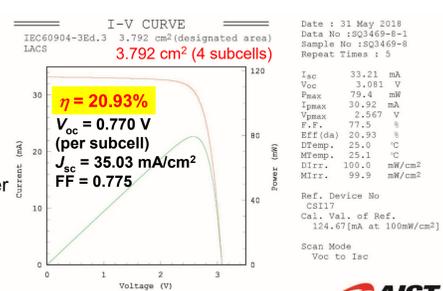


Compared to the reference module with ZnO/AZO,

ZnO/IWOH: Improved  $J_{sc} \times FF$  with the same  $V_{oc}$

IGZO/IWOH: Poor  $V_{oc}$  in the relaxed state ( $\leftarrow$  recombination through midgap states in a-IGZO?)

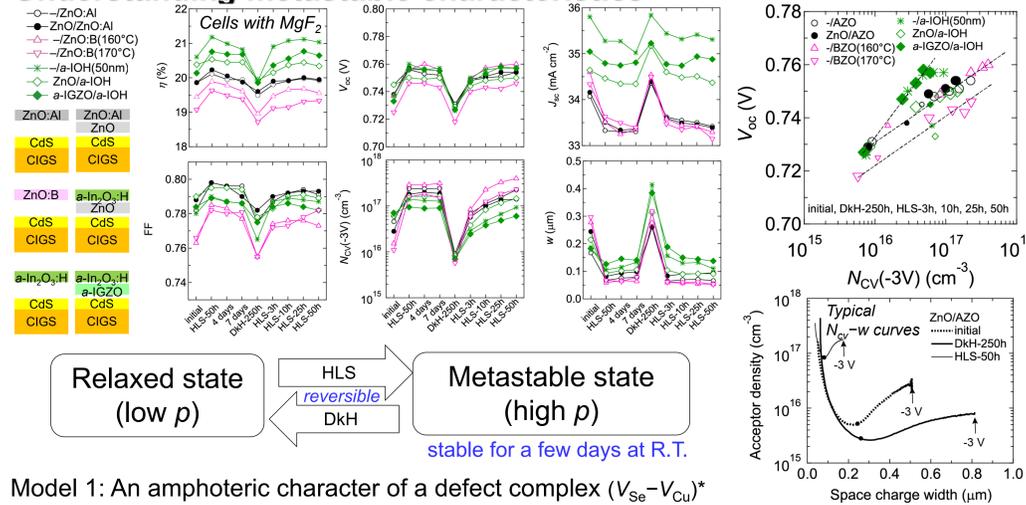
### Certified I-V curve for the mini-module with ZnO/IWOH



High  $J_{sc} \times FF$  is demonstrated by high- $\mu$  IWOH TCO layer

## For further improvement...

### Understanding metastable characteristics



### Module structure

Conventional: In<sub>2</sub>O<sub>3</sub>(thick)/TOS(widegap)/CdS/CIGS/Mo/SLG  
Task: A barrier caused by  $\Delta E_c$  formed at TOS/TCO may affect the transport. i.e., Mg<sub>x</sub>Zn<sub>1-x</sub>O or a-In<sub>x</sub>Ga<sub>1-x</sub>O/In<sub>2</sub>O<sub>3</sub>-based TCO

Gridded: Grid metal/In<sub>2</sub>O<sub>3</sub>(thin)/CdS/CIGS/Mo/SLG

